

SnO₂/TiO₂ thin film n-n heterostructures for H₂ and NO₂ gas sensing

Piotr Nowak¹, Wojciech Maziarz¹, Artur Rydosz¹, Kazimierz Kowalski², Katarzyna Zakrzewska¹

¹ *AGH University of Science and Technology, Faculty of Computer Science, Electronics and Telecommunications, Al. Mickiewicza 30, 30-059 Krakow, Poland,*

² *AGH University of Science and Technology, Faculty of Metals Engineering and Industrial Computer Science, Al. Mickiewicza 30, Krakow*
Piotr.Nowak@agh.edu.pl

Abstract:

Pure SnO₂ and SnO₂/TiO₂ heterostructure based gas sensors for reducing H₂ and oxidizing NO₂ in the temperature range of 80 – 400°C were investigated. SnO₂ thin films were prepared by RF magnetron sputtering, whereas TiO₂ layers were deposited using a relatively less exploited Langmuir-Blodgett (L-B) technique. TiO₂ thin films were characterized with different spectroscopy and imaging methods (XPS, XRD, EDS, SEM, optical profilometry) which confirmed the presence of TiO₂ on the SnO₂ surfaces. The resistance change of SnO₂/TiO₂ system is higher than that of pure SnO₂ thin films for both H₂ and NO₂ gases. Additional TiO₂ layers significantly improve the response of SnO₂/TiO₂ gas sensors (in comparison to pure SnO₂) in the range of 200-400°C even for low concentrations of NO₂. It suggests SnO₂/TiO₂ heterostructure based sensors obtained using combined sputtering/L-B methods can be highly sensitive for H₂ and NO₂.

Key words: gas sensors, n-n heterostructures, SnO₂/TiO₂, thin films, nitrogen dioxide

Introduction

TiO₂ and SnO₂ materials are among the most common metal oxides used for gas sensing [1-3]. The possibility to use different structures and preparation methods (physical and chemical) of TiO₂ and SnO₂ based gas sensors was widely investigated [4-6]. In this paper we discuss the Langmuir-Blodgett (L-B) method - an emerging technique [7] in electronic applications which allows to prepare TiO₂ ultra-thin films at room temperature without modification of the substrate. In this paper we compare properties of pure SnO₂ and SnO₂/TiO₂ heterostructures, and their responses to reducing H₂ and oxidizing NO₂ gases.

Material preparation and measurements

SnO₂ thin films were deposited onto special substrates with defined interdigital electrodes by RF magnetron sputtering from Sn target (20% O₂, 180°C, 50 W, 30 min). The SnO₂ layer was 200 nm thick. The TiO₂/SnO₂ structures were obtained by depositing TiO₂ thin films on previously prepared SnO₂ substrates using Langmuir-Blodgett technique (nanopowder of rutile was a starting material). The processes

were performed using Langmuir KSV NIMA trough (Biolin Scientific company, Sweden) at room temperature and under normal pressure. Gas sensitivity measurements were carried out in a gas chamber with a volume of about 30 cm³ over the range of temperatures between 80 and 400°C [5]. The sensors were exposed to NO₂ and H₂ gases at different concentration levels.

Results

Thin layers of TiO₂ obtained using the L-B method were characterized with SEM, XPS, XRD, EDS and optical profilometry methods. The XPS spectrum and SEM image of the TiO₂ layer is presented in Figure 1.

The SnO₂/TiO₂ heterostructure shows higher resistance than that of pure SnO₂ thin films but an additional TiO₂ layer increases the response to both reducing and oxidizing gases. Figure 2 shows the response of the SnO₂/TiO₂ system compared to pure SnO₂ based sensor at 400°C within the H₂ concentration range from 15 to 325 ppm. It was observed that even for the smallest H₂ concentrations, there is an increase in the response of the SnO₂/TiO₂ sensor in relation to the pure SnO₂ thin film. Both

materials are n-type semiconductors thus the resistance R of the sensors drops under exposure to reducing H_2 gas, while it rises under exposure to oxidizing NO_2 gas.

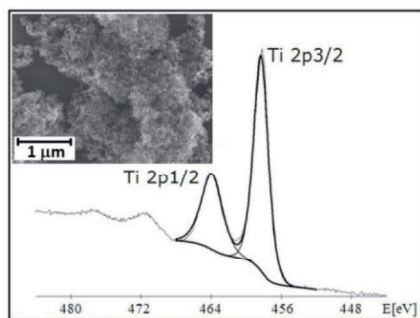


Fig. 1. Characteristic XPS peaks for Ti^{4+} in TiO_2 thin film obtained from nanopowder of rutile, SEM of TiO_2 layers on the silica substrate (inset)

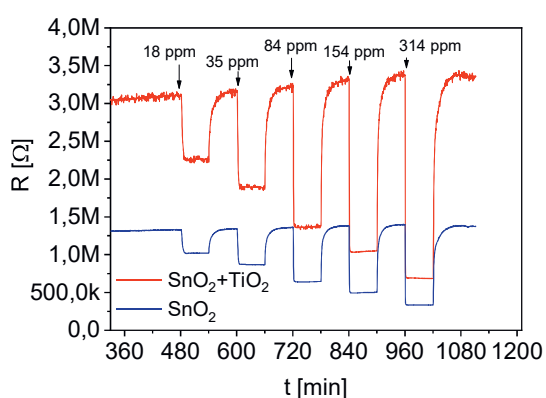


Fig. 2. Resistance changes of SnO_2/TiO_2 and pure SnO_2 thin films to H_2 at $400^\circ C$

Despite the significant increase in the SnO_2/TiO_2 system resistance compared to pure SnO_2 sensor the response was improved by the TiO_2 thin layer addition (Figure 2).

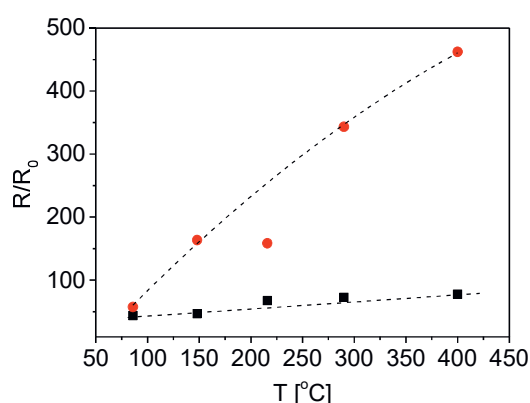


Fig. 3. The responses of pure SnO_2 and SnO_2/TiO_2 heterostructure based gas sensors to 20 ppm of NO_2 at $400^\circ C$

For SnO_2 sensors, the response defined as a ratio of sensor resistance R in NO_2 to resistance R_0 in air is of about $R/R_0 = 70$, whereas for SnO_2/TiO_2 system R/R_0 increases to 450 (at $400^\circ C$).

Conclusions

Spectroscopy and imaging methods used to characterize the investigated samples clearly indicate the proposed L-B technique is effective for depositing of TiO_2 thin films. Moreover, L-B, in contrast to physical vapour methods, is a non-destructive procedure which does not damage the SnO_2 substrates. The heterostructures obtained by depositing an additional TiO_2 thin layer on SnO_2 thin films have higher gas response than pure SnO_2 for both reducing (H_2) and oxidizing (NO_2) gases. It seems that SnO_2/TiO_2 based gas sensor is highly sensitive even to low concentrations of NO_2 gas. The significant response increase was observed especially over the range of $200^\circ C - 400^\circ C$.

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